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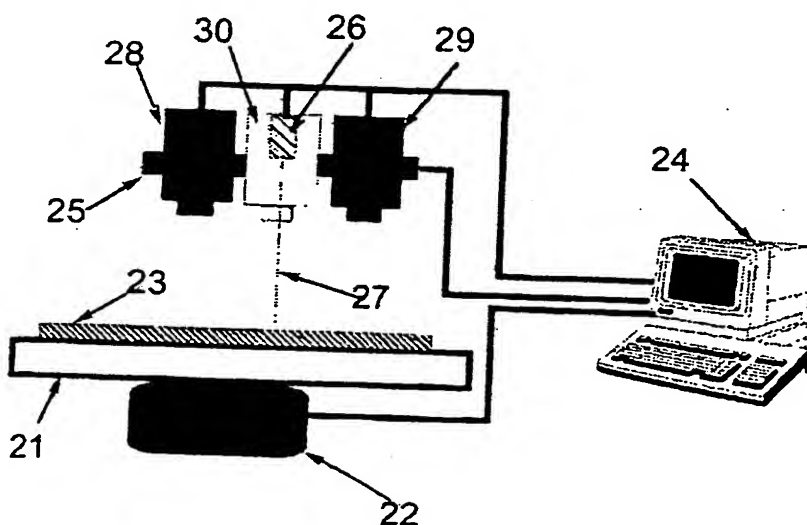
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(54) Title: **CONFOCAL WAFER-INSPECTION SYSTEM AND METHOD**



(57) Abstract: A confocal wafer inspection system comprising: (a) a table to carry a wafer for inspection, said table has two vertical degrees of freedom to enable XY axis movements; (b) a movement means for moving said table along said degrees of freedom; (c) a confocal height measurement system, perpendicular to said table, for measuring the range to a point on a surface of said wafer and for enabling to recognize changes in surface altitude while said wafer moves with said table; and (d) a computer operative for: (i) holding a bumps map of said wafer; (ii) controlling said movement means; (iii) moving said table so that the measuring point of said confocal height measurement system crosses each bump of said wafer; (iv) storing height profile of each bump; (v) comparing said height profiles or checking each height profile according to predetermined criteria or both; and (vi) enabling results output. The invention also relates to a method for confocal wafer inspection.

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